

Appl. No. 09/786,600
Atty. Docket No. CM2011
Amdt. dated 06/10/2003
Reply to Office Action of 2/12/03

AMENDMENTS TO THE SPECIFICATION

Please amend the specification as follows:

Please replace the paragraph beginning at page 3, line 9, with the following rewritten paragraph:

B1

— Plasma coating processes of metals, polymers, and other textile substrates, with fluorocarbon films are known in the art. As an example, it is known from USP U.S. Pat. No. 4,869,922 and from other sources, that deposition from continuous (i.e. non modulated) radiofrequency (RF) glow discharges fed with fluorocarbons provides films, layers, tapes, plates, and differently shaped articles made of plastics, metals or other materials, with a thin fluorocarbon coating, with no other material interposed between the coating itself and the substrate. Such coatings are claimed to have very good adherence to the items processed, to be void-free, to be uniform or not porous, and to show controlled wettability characteristics, which depend on their surface chemical composition. The non modulated, continuous plasma process of the above mentioned patent leads to coatings characterized by static water contact angle (WCA) values lower than 120°.--

Please replace the paragraph beginning at page 3, line 22, with the following rewritten paragraph:

B2

— Glow discharges treatments are also considered in US-A U.S. Pat. No. 5,462,781 for improving the bondability of an implantable polymer medical device or for changing the wettability of a polymer fabric. Several of the references discussed in this patent confirm non modulated, continuous plasma treatments as a means for varying the inherent WCA of a surface. -

Please replace the paragraph beginning at page 3, line 28, with the following rewritten paragraph:

B3

— US-A U.S. Pat. No. 5,034,265 discloses a non modulated, continuous plasma treatment for improving the biocompatibility of vascular grafts with a CF_x fluorocarbon coating deposited at the inside wall of the grafts in a proper plasma reactor fed with tetrafluoroethylene (C_2F_4 , TFE) at 0.2 Torr. In the preferred embodiment of the invention no other materials are interposed between the substrate and the coating.

Please replace the paragraph beginning at page 4, line 8, with the following rewritten paragraph:

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B4

-- U.S. Pat. No. 5,262,208 discloses an gas plasma treatment for archival preservation of paper manuscripts by a thin film protective polymer film. The treatment time is ranging from 30-3600 seconds. Other methods have been used to obtain thin coatings on the web materials with short treatment periods. Providing surface treatment is disclosed in ~~US Patent No.~~ U.S. Pat. Nos. 4,842,893 and 4,954,371 which describe a process for high speed coating of substrates with a complete and uniformly adhering layer and using electron beam radiation curing of the vapor deposited monomers for multilayer capacitors. U.S. Pat. No. 4,842,893 discloses high speed coating process including flash vaporization system and electron beam curing. Both of these electron beam disclosures are incorporated herein by reference. Other uses of electron beam coatings in the electronic industry field have been reported by Westinghouse science & technology center USA (Adv. Mat. Newsletter Volume 13, No 9, 1991 page 4). --